

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

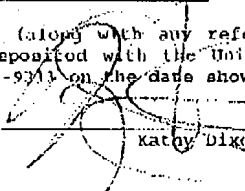
| | |
|--|---|
| Applicant(s): Chih-Ming Ke | RECEIVED CENTRAL FAX CENTER MAR 11 2004 OFFICIAL |
| Application No.: 10/047,266 (CONF 4511) | |
| Filed: 1/14/2002 | |
| Title: Reducing photoresist shrinkage via plasma treatment | |
| Attorney Docket No.: 67,200-641 | Group Art Unit: 1765 Examiner: Kin Chan Chen |

Commissioner for Patents
Alexandria, VA 22313-1450

Certificate of Facsimile Transmission

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Patent Office via facsimile no. (703) 872-9311 on the days shown below.

Date: Mar. 11, 2004


Kathy Dixon

o.k to enter.
3/18/04 K-CC

SUPPLEMENTAL AMENDMENT

Dear Sir:

In response to an Advisory Action mailed March 5, 2004, and as a result of a telephone conference with Examiner Chen on March 11, 2004, please enter the following amendments and consider the following remarks.